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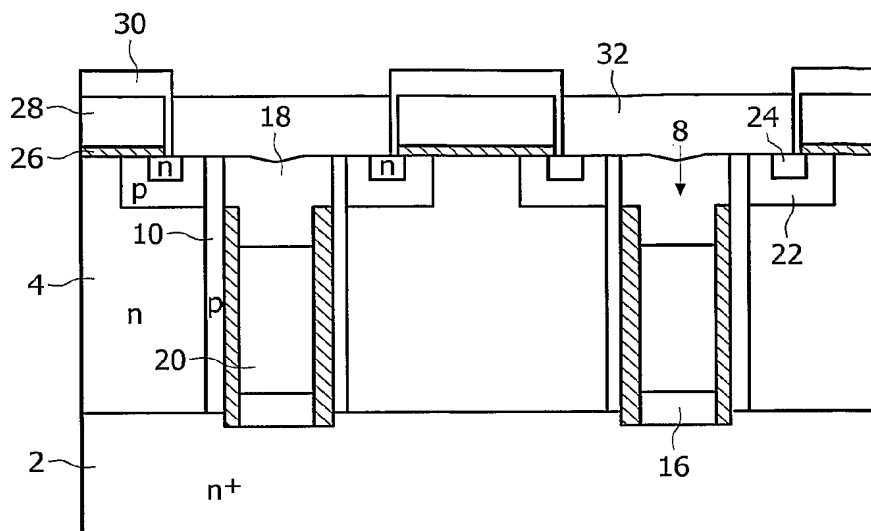
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(54) Title: TRENCH SEMICONDUCTOR DEVICE AND METHOD OF MANUFACTURING IT



(57) Abstract: A RESURF type semiconductor device is manufactured having a drift region (4) over a drain region (2). Trenches (8) are formed through openings in mask (6). A trench insulating layer (12) is deposited on the sidewalls and base of the trenches followed by an overetching step to remove the trench insulating layer (10) from the base of the trenches as well as the top of the sidewalls of the trenches adjacent to the first major surface leaving exposed silicon at the top of the sidewalls of the trench and the base of the trenches. Silicon is selectively grown plugging the trenches with silicon plug (18) leaving void (20).

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